

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-19 (Canceled):

Claim 20 (Previously Presented): A developing apparatus comprising:

a rotatable spin chuck configured to hold a substrate having a light-exposed resist film disposed thereon;

a developing solution nozzle configured to supply a predetermined developing solution for developing the resist film onto a surface of the substrate held by the spin chuck;
a rinsing nozzle configured to supply a rinsing liquid onto a surface of the substrate held by the spin chuck;

a chemical liquid nozzle configured to supply a chemical liquid onto a surface of the substrate held by the spin chuck, wherein the chemical liquid contains a resist curing aid contributory to curing of a resist film remaining on the substrate after a developing reaction;

a shifting mechanism configured to move the developing solution nozzle, the rinsing nozzle, and the chemical liquid nozzle relative to the substrate held by the spin chuck; and

a light radiation mechanism configured to radiate light having a predetermined wavelength onto a surface of the substrate held by the spin chuck, wherein the developing solution nozzle has a structure elongated in one direction and configured to deliver the developing solution essentially as a strip extending in a longitudinal direction thereof,

the chemical liquid nozzle has a structure elongated in one direction and configured to discharge the chemical liquid essentially as a strip extending in a longitudinal direction thereof,

the developing solution nozzle and the chemical liquid nozzle are integrated in parallel with each other,

the light radiation mechanism comprises a casing elongated in one direction and having a slit to radiate light essentially as a strip extending in a longitudinal direction thereof, and a light source of a predetermined wavelength disposed in the casing, and

the casing and the chemical liquid nozzle are integrated in parallel with each other.

Claim 21 (Canceled).

Claim 22 (Canceled).

Claim 23 (Previously Presented): The developing apparatus according to claim 20, wherein the rinsing nozzle has a structure elongated in one direction and configured to discharge the rinsing liquid essentially as a strip extending in a longitudinal direction thereof, and

the rinsing nozzle and the chemical liquid nozzle are integrated in parallel with each other.

Claim 24 (Canceled).

Claim 25 (Currently Amended): A developing apparatus comprising:
a rotatable spin chuck configured to hold a substrate having a light-exposed resist film
disposed thereon;
a developing solution nozzle configured to supply a predetermined developing
solution for developing the resist film onto a surface of the substrate held by the spin chuck;

a rinsing nozzle configured to supply a rinsing liquid onto a surface of the substrate held by the spin chuck;

a chemical liquid nozzle configured to supply a chemical liquid onto a surface of the substrate held by the spin chuck, wherein the chemical liquid contains a resist curing aid contributory to curing of a resist film remaining on the substrate after a developing reaction;

a shifting mechanism configured to move the developing solution nozzle, the rinsing nozzle, and the chemical liquid nozzle relative to the substrate held by the spin chuck; and

a light radiation mechanism configured to radiate light having a predetermined wavelength onto a surface of the substrate held by the spin chuck ~~The developing apparatus according to Claim 20;~~

wherein the chemical liquid nozzle comprises a casing elongated in one direction, which has a chemical liquid cell to store the chemical liquid therein, and a discharge port to discharge the chemical liquid essentially as a strip extending in a longitudinal direction thereof from the chemical liquid cell,

the light radiation mechanism comprises a casing elongated in one direction and having a slit to radiate light essentially as a strip extending in a longitudinal direction thereof, and a light source of a predetermined wavelength disposed in the casing, and

the casing of the chemical liquid nozzle and the casing of the light radiation mechanism are integrated in parallel with each other.

Claims 26-35 (Canceled).

Claim 36 (Previously Presented): A developing apparatus comprising:
a rotatable spin chuck configured to hold a substrate having a light-exposed resist film disposed thereon;

a developing solution nozzle configured to supply a predetermined developing solution for developing the resist film onto a surface of the substrate held by the spin chuck;

a rinsing nozzle configured to supply a rinsing liquid onto a surface of the substrate held by the spin chuck;

a chemical liquid nozzle configured to supply a chemical liquid onto a surface of the substrate held by the spin chuck, wherein the chemical liquid contains a resist curing aid contributory to curing of a resist film remaining on the substrate after a developing reaction;

a shifting mechanism configured to move the developing solution nozzle, the rinsing nozzle, and the chemical liquid nozzle relative to the substrate held by the spin chuck; and

a light radiation mechanism configured to radiate light having a predetermined wavelength onto a surface of the substrate held by the spin chuck, wherein

the rinsing nozzle has a structure elongated in one direction and configured to discharge the rinsing liquid essentially as a strip extending in a longitudinal direction thereof,

the chemical liquid nozzle has a structure elongated in one direction and configured to discharge the chemical liquid essentially as a strip extending in a longitudinal direction thereof,

the rinsing nozzle and the chemical liquid nozzle are integrated in parallel with each other,

the light radiation mechanism comprises a casing elongated in one direction and having a slit to radiate light essentially as a strip extending in a longitudinal direction thereof, and a light source of a predetermined wavelength disposed in the casing, and

the casing and the chemical liquid nozzle are integrated in parallel with each other.

Claim 37 (Canceled).

Claim 38 (Canceled).

Claim 39 (Previously Presented): The developing apparatus according to claim 25, wherein the developing solution nozzle has a structure elongated in one direction and configured to deliver the developing solution essentially as a strip extending in a longitudinal direction thereof, and

the developing solution nozzle and the chemical liquid nozzle are integrated in parallel with each other.